

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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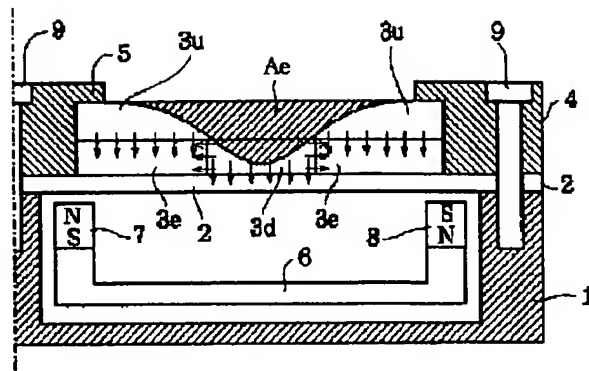
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APPLICATION NUMBER : 05286502

APPLICANT : NISSHIN STEEL CO LTD;

INVENTOR : SAITO MINORU;

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TITLE : CATHODE FOR MAGNETRON  
SPUTTERING



ABSTRACT : PURPOSE: To provide the target for a magnetron sputtering device which is inexpensively produced, has high utilization efficiency and permits easy mounting to the cathode and exchanging.

CONSTITUTION: The target is divided to an upper member 3<sub>u</sub> and a lower member 3<sub>d</sub> with respect to a thickness direction and the lower member 3<sub>d</sub> is inserted between the upper member 3<sub>u</sub> and the backing plate 2. The upper member 3<sub>u</sub> is press welded and fixed by a target holder 4 to a backing plate 2. The lower member 3 may be further divided to the lower member 3<sub>d</sub> to be subjected to erosion and a peripheral member 3<sub>e</sub>. A member formed of a material having a good thermal conductivity is used as the peripheral member 3<sub>e</sub> and may be provided with a function as the backing plate as well. As a result, the target is formed as a segmental type meeting the shape of the erosion and, therefore, the ratio at which the target is effectively consumed as sputtered particles is high and the assembly and exchange, etc., are easy.

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